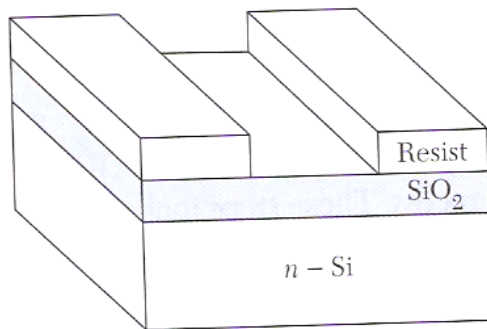
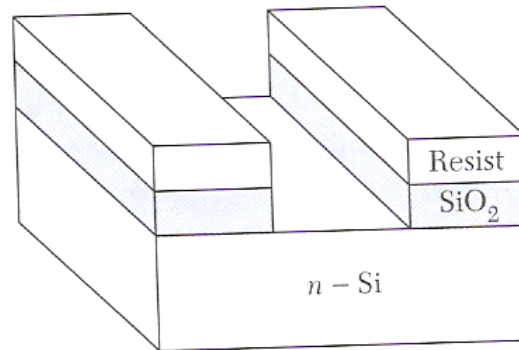


pn-junctions

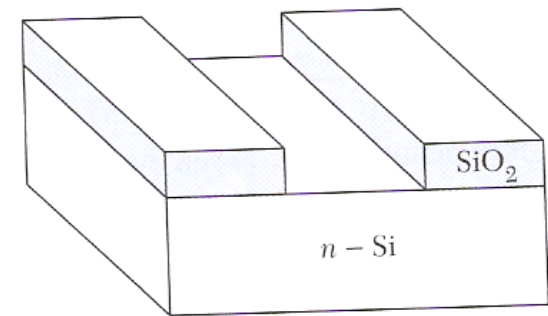
diode fabrication



(a)

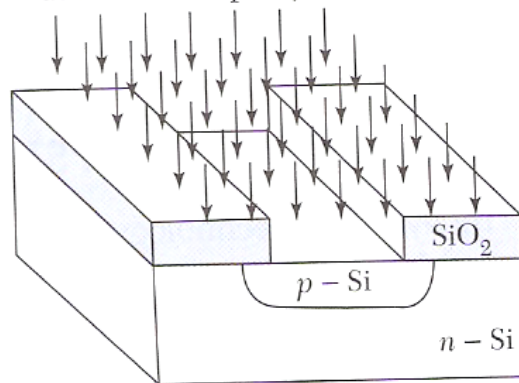


(b)

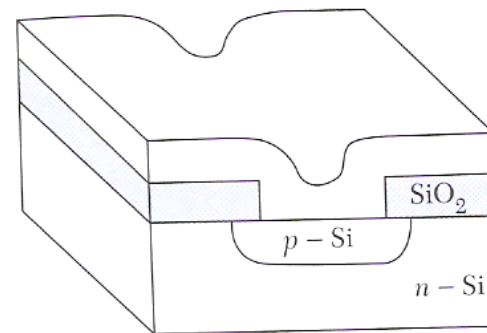


(c)

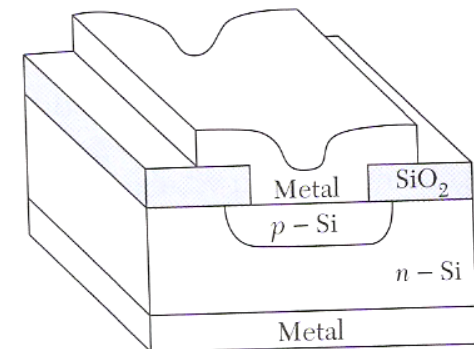
Dopant gas
or
accelerated impurity ions



(d)

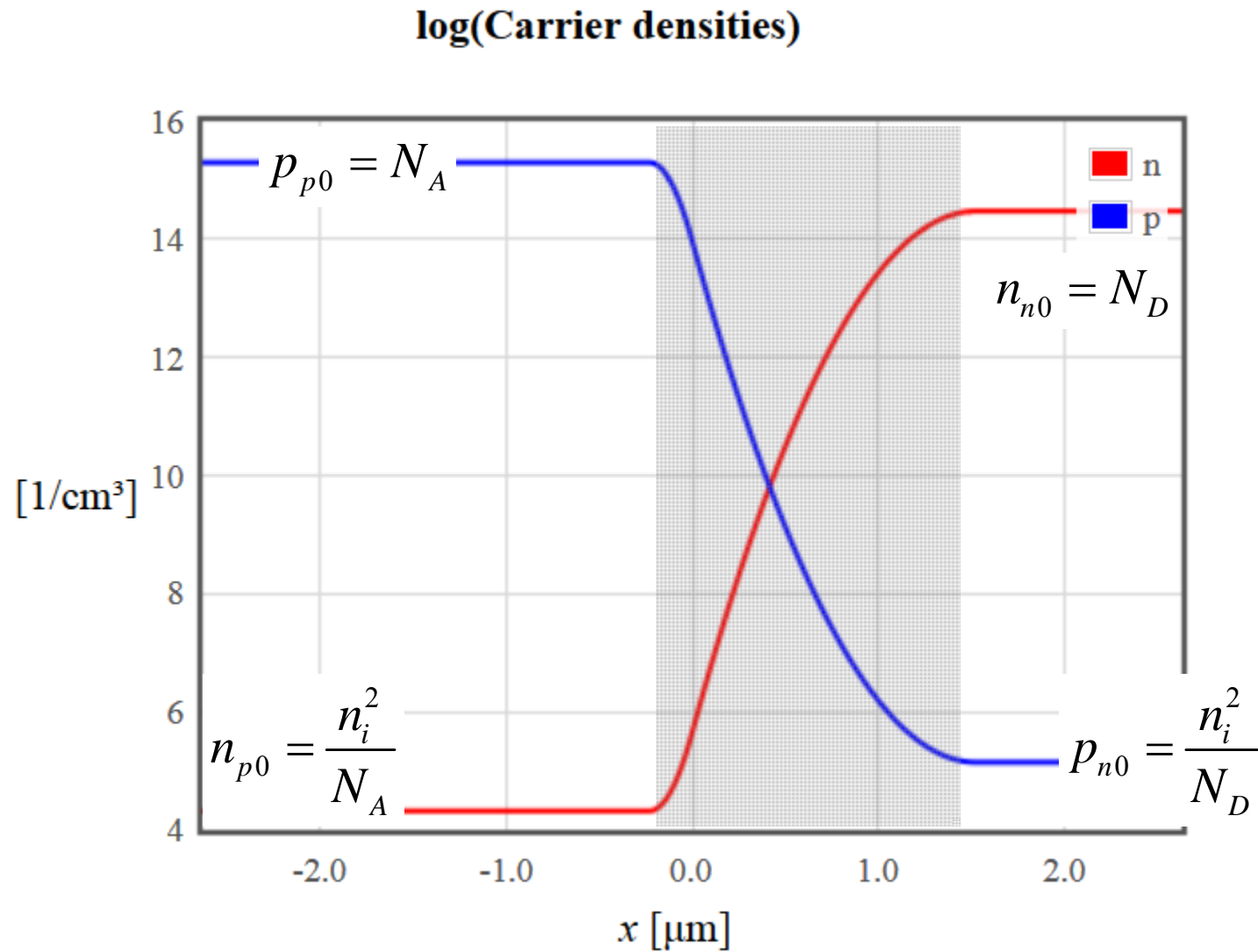


(e)



(f)

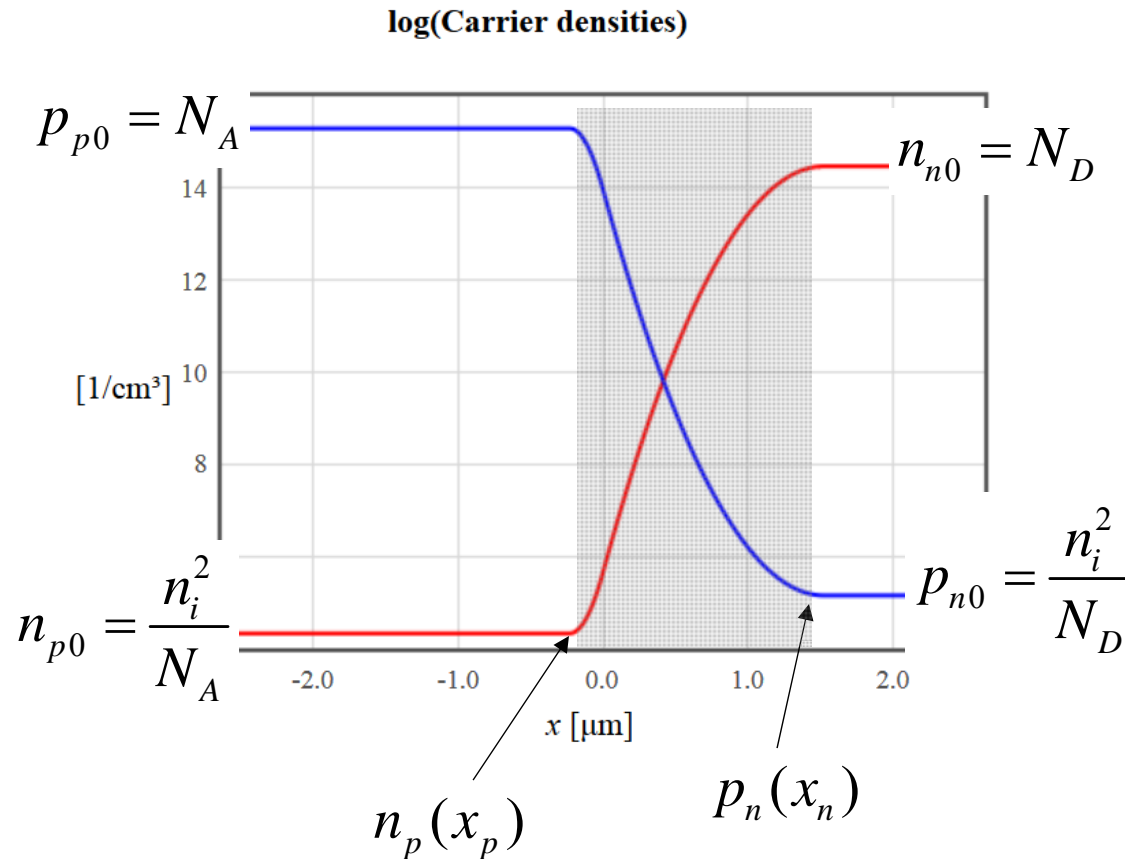
Equilibrium concentrations, $V = 0$



$$n_{p0}p_{p0} = n_{n0}p_{n0} = n_i^2$$

Bias voltage, $V = 0$

$$eV_{bi} = k_B T \ln \left(\frac{N_D N_A}{n_i^2} \right) = k_B T \ln \left(\frac{N_D}{n_{p0}} \right) = k_B T \ln \left(\frac{N_A}{p_{n0}} \right)$$



$$n_{p0} p_{p0} = n_{n0} p_{n0} = n_i^2$$

$V = 0$

$$n_{p0} = N_D \exp \left(\frac{-eV_{bi}}{k_B T} \right)$$

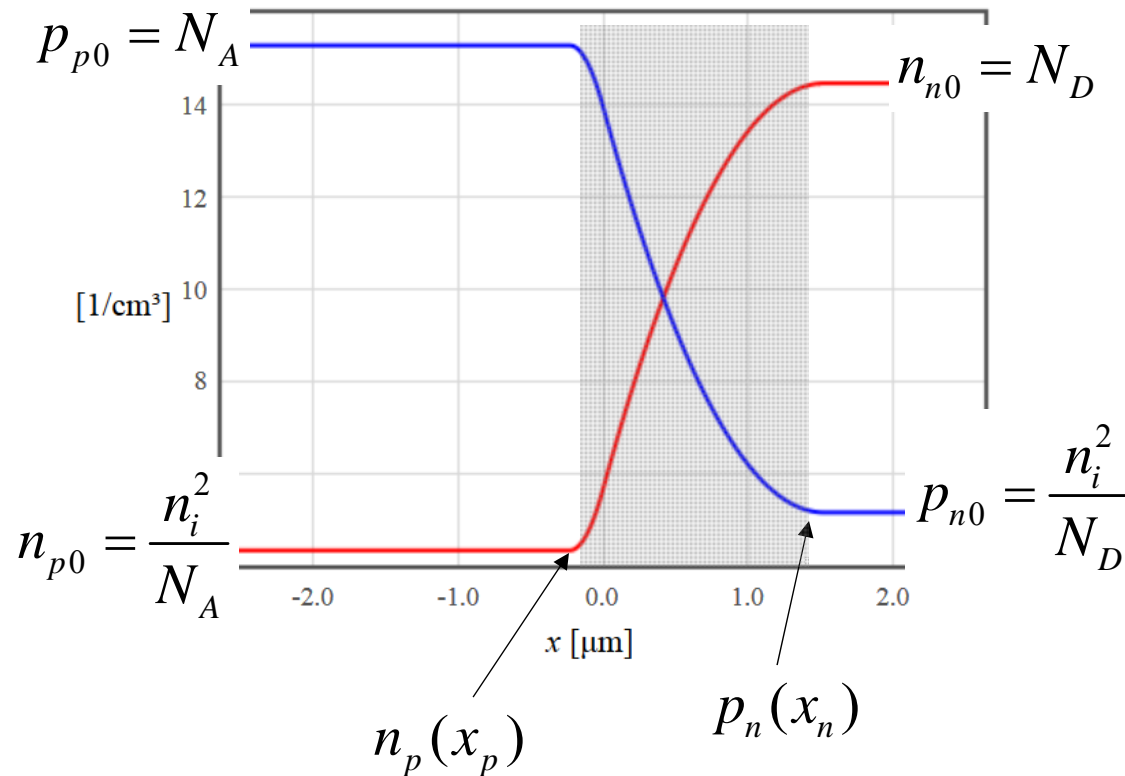
$$p_{n0} = N_A \exp \left(\frac{-eV_{bi}}{k_B T} \right)$$

Bias voltage, $V \neq 0$

$$eV_{bi} = k_B T \ln\left(\frac{N_D N_A}{n_i^2}\right) = k_B T \ln\left(\frac{N_D}{n_{p0}}\right) = k_B T \ln\left(\frac{N_A}{p_{n0}}\right)$$

$$n_{p0} p_{p0} = n_{n0} p_{n0} = n_i^2$$

log(Carrier densities)



$$V = 0$$

$$n_{p0} = N_D \exp\left(\frac{-eV_{bi}}{k_B T}\right)$$

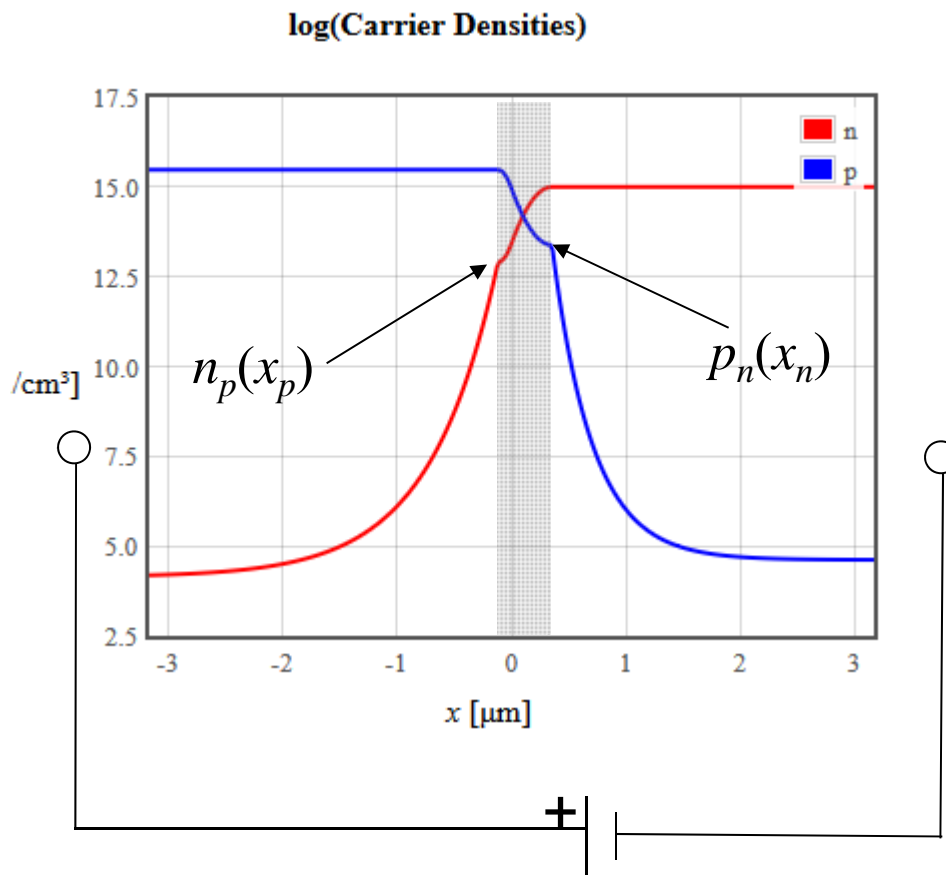
$$p_{n0} = N_A \exp\left(\frac{-eV_{bi}}{k_B T}\right)$$

$$V \neq 0$$

$$n_p(x_p) = N_D \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

$$p_n(x_n) = N_A \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

Forward bias, $V > 0$



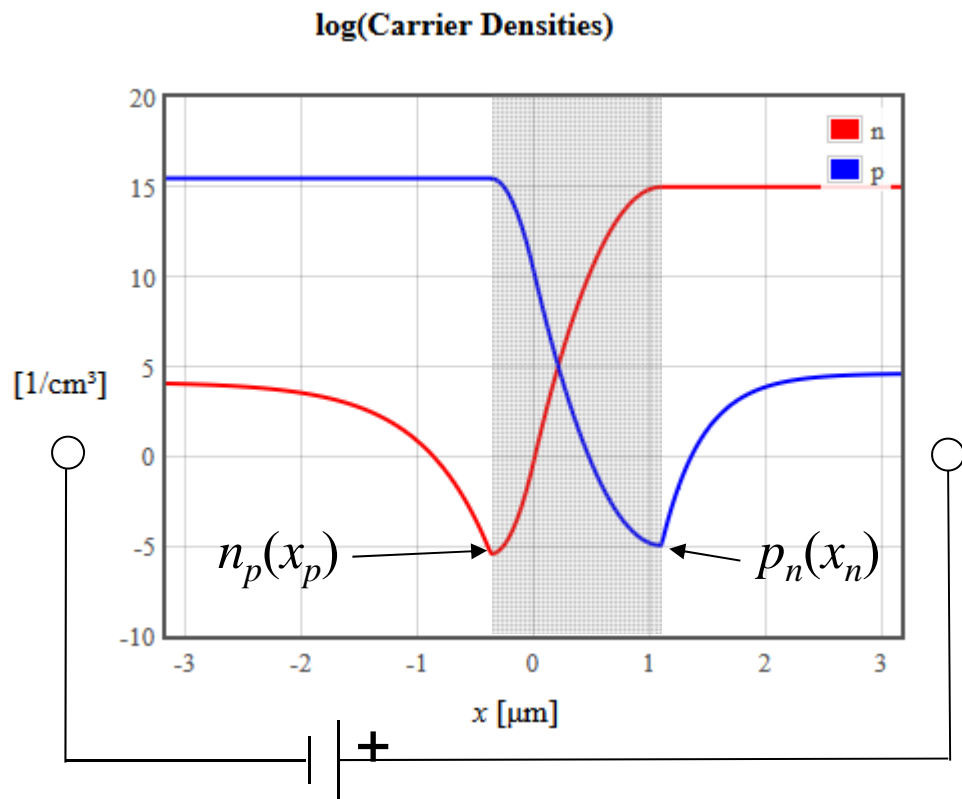
Electrons and holes are driven towards the junction.
The depletion region becomes narrower

$$n_p(x_p) = N_D \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

$$p_n(x_n) = N_A \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

Minority electrons are injected into the p-region
Minority holes are injected into the n-region

Reverse bias, $V < 0$



Electrons and holes are driven away from the junction.

The depletion region becomes wider

$$n_p(x_p) = N_D \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

$$p_n(x_n) = N_A \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

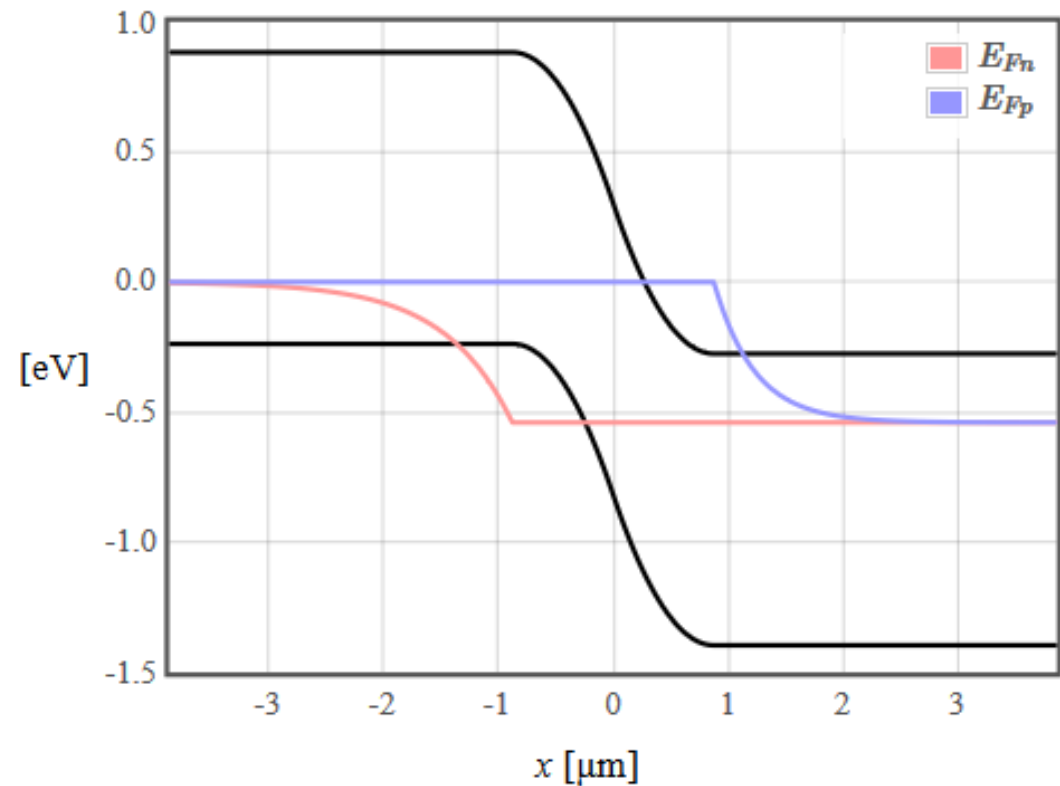
Minority electrons are extracted from the p-region by the electric field
Minority holes are extracted from the n-region by the electric field

Quasi Fermi level

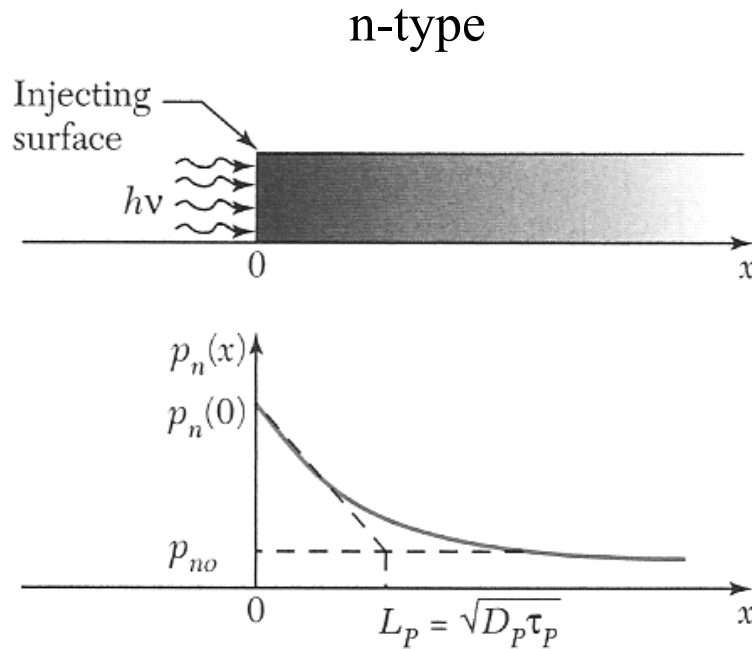
When the charge carriers are not in equilibrium the Fermi energy can be different for electrons and holes.

$$n = N_c \exp\left(\frac{E_{Fn} - E_c}{k_B T}\right)$$

$$p = N_v \exp\left(\frac{E_v - E_{Fp}}{k_B T}\right)$$



Review of Diffusion



$$D_p \frac{\partial^2 p_n}{\partial x^2} = \frac{p_n - p_{n0}}{\tau_p}$$

recombination time

$$p_n(x) = p_{n0} + (p_n(0) - p_{n0}) \exp\left(\frac{-x}{L_p}\right)$$

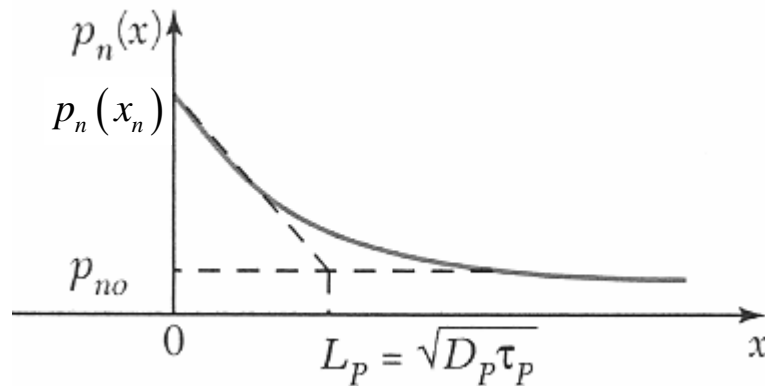
$$L_p = \sqrt{D_p \tau_p}$$

diffusion length

Injection only occurs at the surface. There the minority carrier density is $p_n(0)$.

Diffusion current

n-type



$$p_n(x) = p_{n0} + (p_n(x_n) - p_{n0}) \exp\left(\frac{-x}{L_p}\right)$$

$$J_{diff,p} = -eD_p \frac{dp}{dx}$$

$$J_{diff,p} = -eD_p \frac{dp}{dx} = (p_n(x_n) - p_{n0}) \frac{eD_p}{L_p} \exp\left(\frac{-x}{L_p}\right)$$

At the edge of the depletion region:

$$J_{diff,p} = -eD_p \frac{dp}{dx} = (p_n(x_n) - p_{n0}) \frac{eD_p}{L_p}$$

Diffusion current

$$J_{diff,p} = (p_n(x_n) - p_{n0}) \frac{eD_p}{L_p}$$
$$p_n(x_n) = p_{p0} \exp\left(-\frac{e(V_{bi} - V)}{k_B T}\right)$$

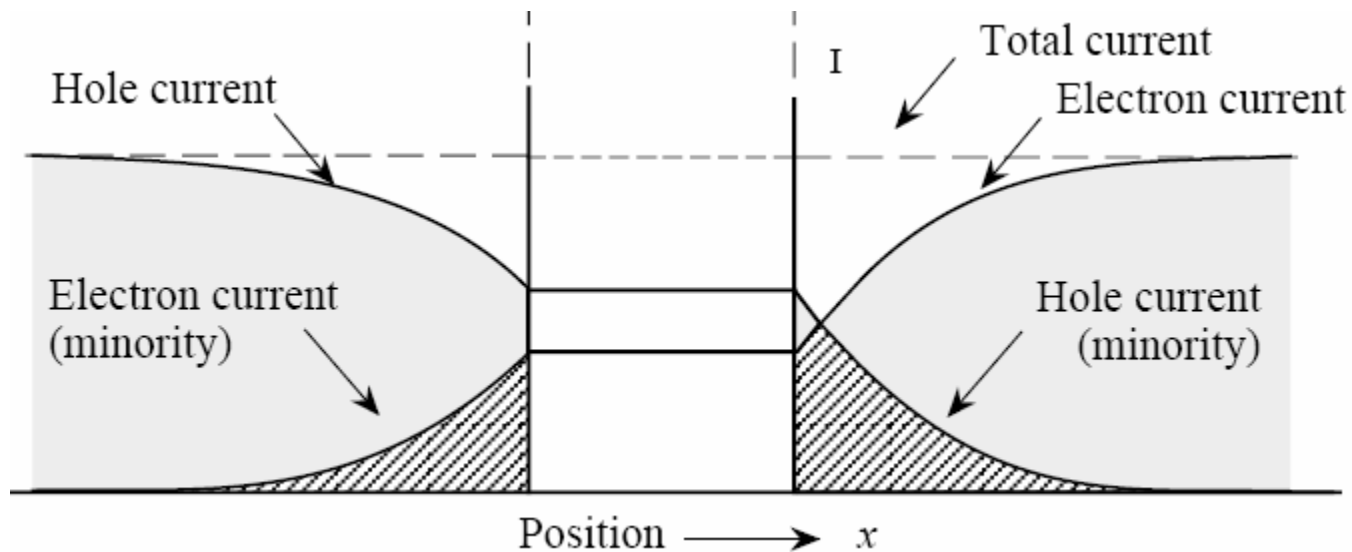
$$J_{diff,p} = \left(p_{p0} \exp\left(-\frac{e(V_{bi} - V)}{k_B T}\right) - p_{n0} \right) \frac{eD_p}{L_p}$$
$$p_{p0} = p_{n0} \exp\left(\frac{eV_{bi}}{k_B T}\right)$$

$$J_{diff,p} = p_{n0} \frac{eD_p}{L_p} \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right)$$

Diffusion current

$$J_{diff,p} = \frac{p_{n0} e D_p}{L_p} \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right)$$

$$J_{diff,n} = \frac{n_{p0} e D_n}{L_n} \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right)$$

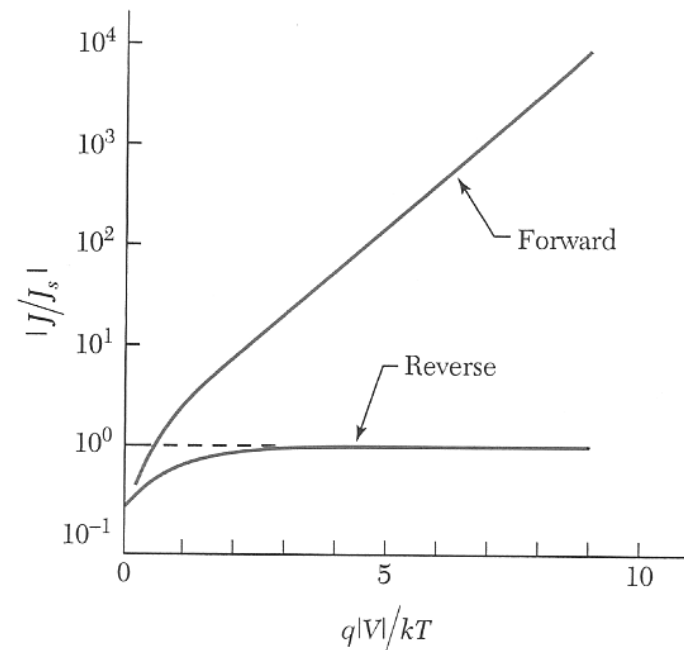
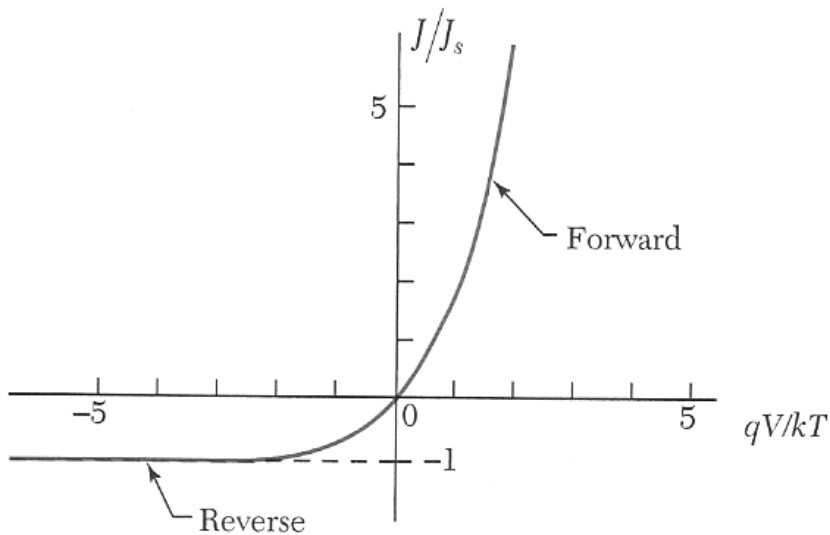


Diode current

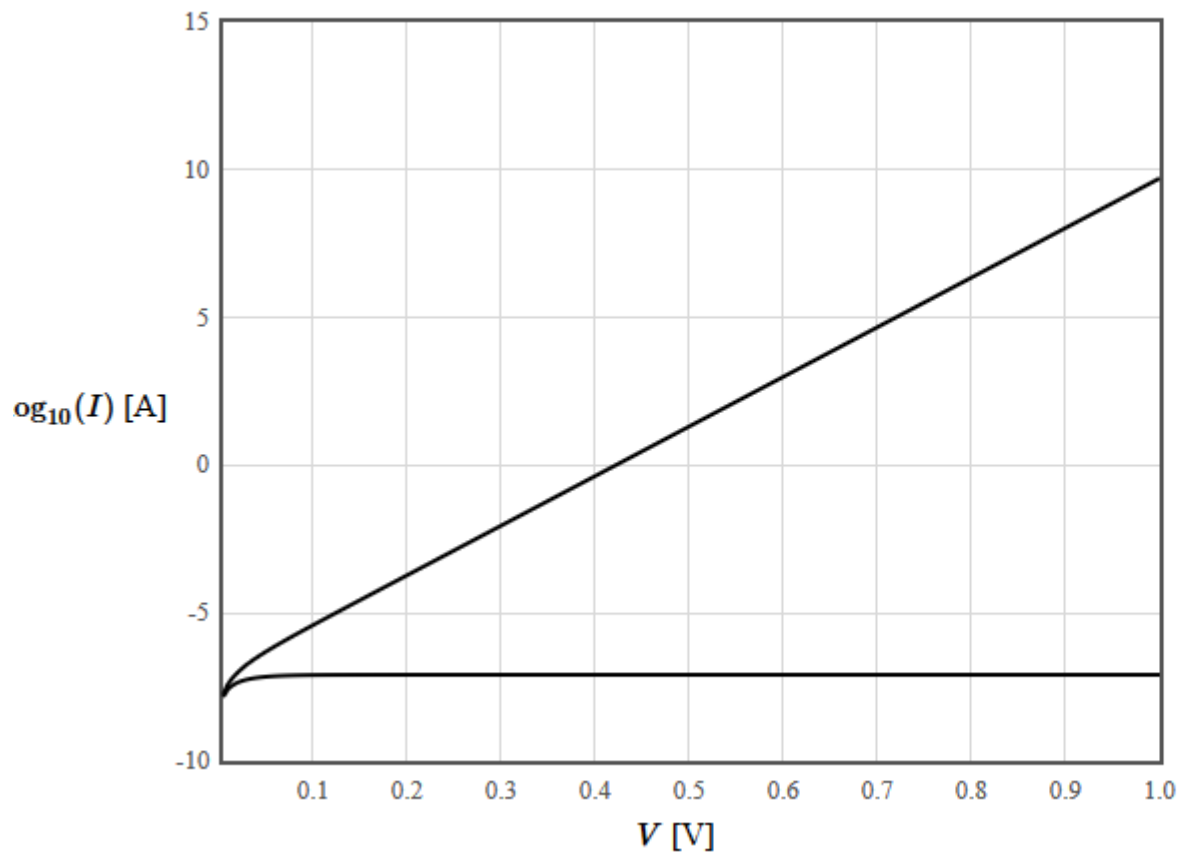
$$I = eA \left(\frac{p_{n0} D_p}{L_p} + \frac{n_{p0} D_n}{L_n} \right) \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right) = I_s \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right)$$

Area

Saturation current



Diode I-V characteristics



Simulation parameters for a diode:

- $A = 1\text{E-}3$ cm²
- $N_c(300\text{K}) = 1.04\text{E}19$ cm⁻³
- $N_v(300\text{K}) = 6.0\text{E}18$ cm⁻³
- $E_g = 0.7437 - 4.77\text{E-}4 * T * T / (T + 235)$ eV
- $\mu_p = 1900$ cm²/Vs
- $\tau_p = 1\text{E-}8$ s
- $N_a = 1\text{E}17$ cm⁻³
- $\mu_n = 3900$ cm²/Vs
- $\tau_n = 1\text{E-}8$ s
- $N_d = 5\text{E}17$ cm⁻³
- $T = 300$ K

Buttons: Replot, Si, **Ge**, GaAs

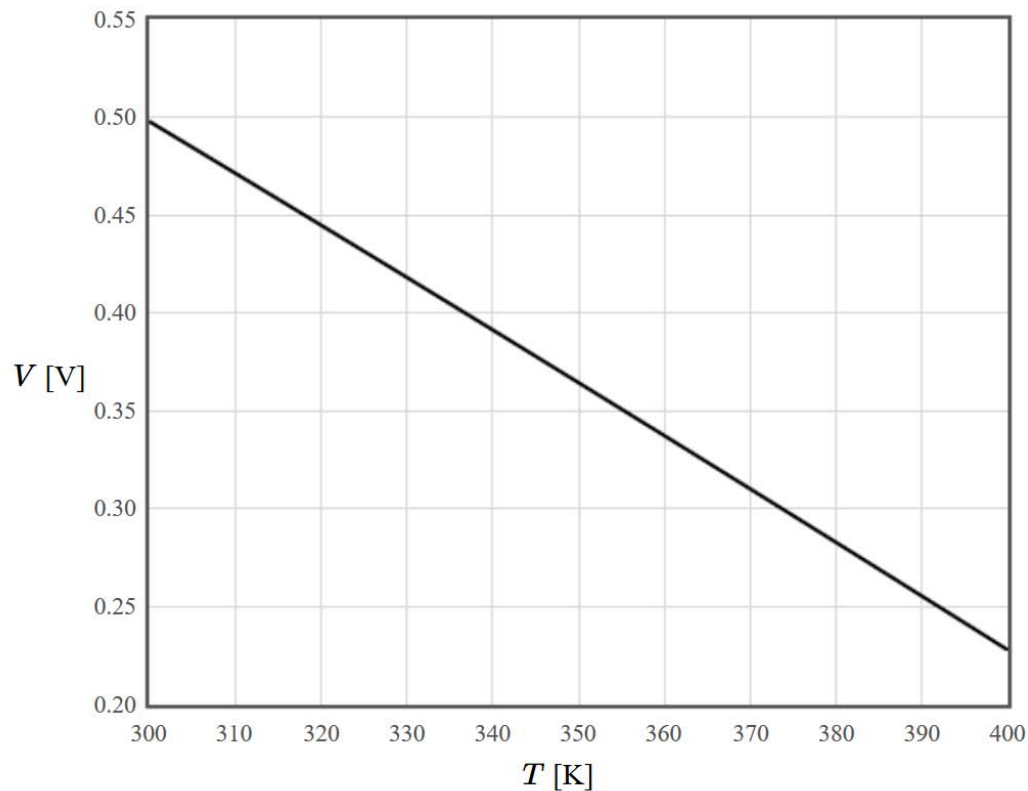
<http://lamp.tu-graz.ac.at/~hadley/psd/L6/pnIV.php>

Thermometer

$$I_S = Aen_i^2 \left(\frac{D_p}{L_p N_d} + \frac{D_n}{L_n N_a} \right)$$

$$n_i = \sqrt{N_c \left(\frac{T}{300} \right)^{3/2} N_v \left(\frac{T}{300} \right)^{3/2} \exp\left(\frac{-E_g}{2k_B T} \right)}$$

$$D_n = \frac{\mu_n k_B T}{e}$$

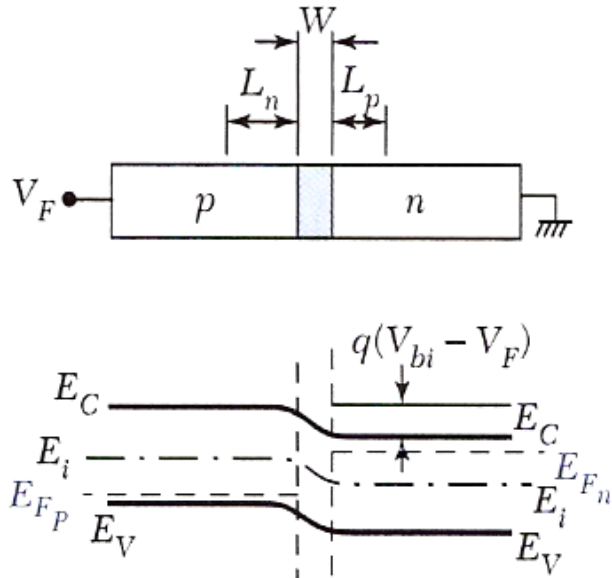


$A = 1E-3$ cm²
 $N_c(300K) = 2.78E19$ cm⁻³
 $N_v(300K) = 9.84E18$ cm⁻³
 $E_g = 1.166-4.73E-4*T*(T+636)$ eV
 $\mu_p = 480$ cm²/Vs
 $\tau_p = 1E-8$ s
 $N_a = 1E17$ cm⁻³
 $\mu_n = 1350$ cm²/Vs
 $\tau_n = 1E-8$ s
 $N_d = 5E17$ cm⁻³
 $T_{start} = 300$ K
 $T_{stop} = 400$ K
 $I = 1E-6$ A

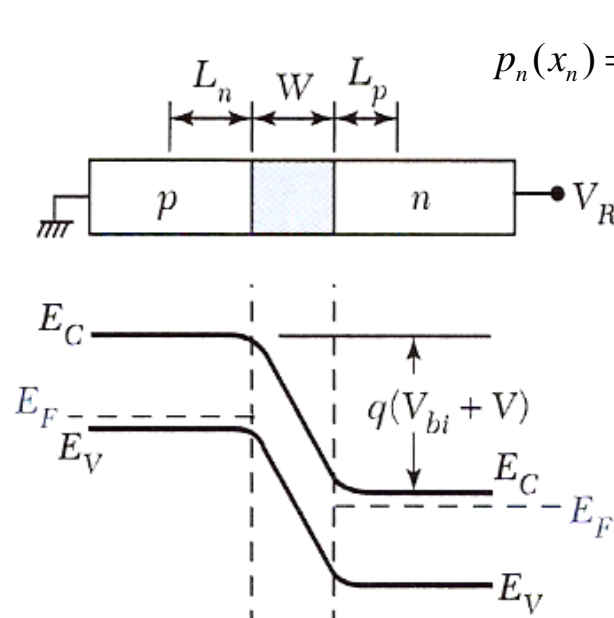
Replot

Si Ge GaAs

Forward



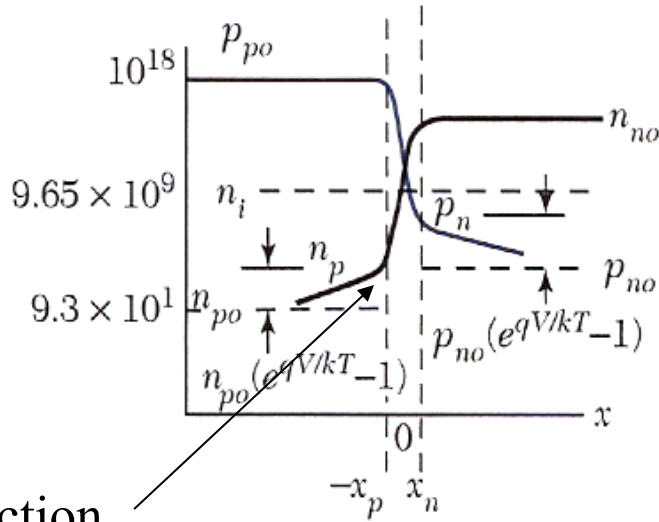
Reverse



$$n_p(x_p) = N_D \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

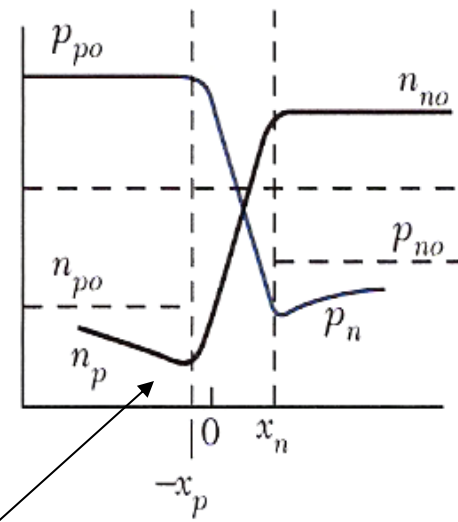
$$p_n(x_n) = N_A \exp\left(\frac{-e(V_{bi} - V)}{k_B T}\right)$$

$J_{diff} > J_{drift}$



Injection

$J_{diff} < J_{drift}$

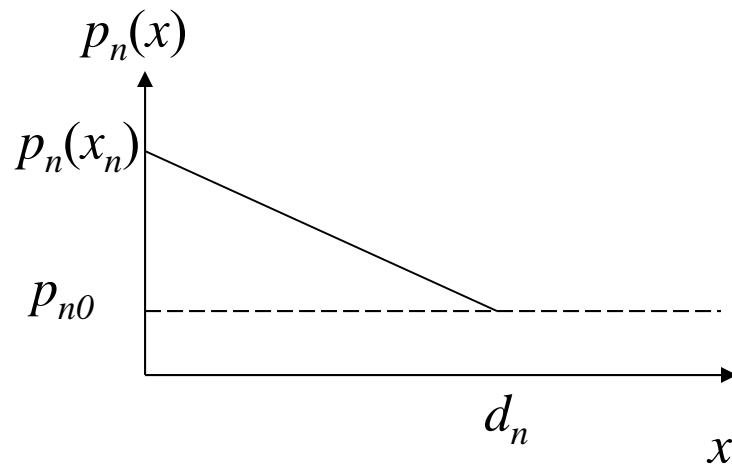


Extraction

Short diode

n-type

$$d_n \ll L_p$$



Metal contact is much closer to the depletion region than the diffusion length

$$J_{diff,p} = -eD_p \frac{dp}{dx}$$

$$J_{diff,p} = -eD_p \frac{dp}{dx} = \frac{eD_p}{d_n} (p_n(x_n) - p_{n0})$$

Diffusion current

$$J_{diff,p} = (p_n(x_n) - p_{n0}) \frac{eD_p}{d_n}$$

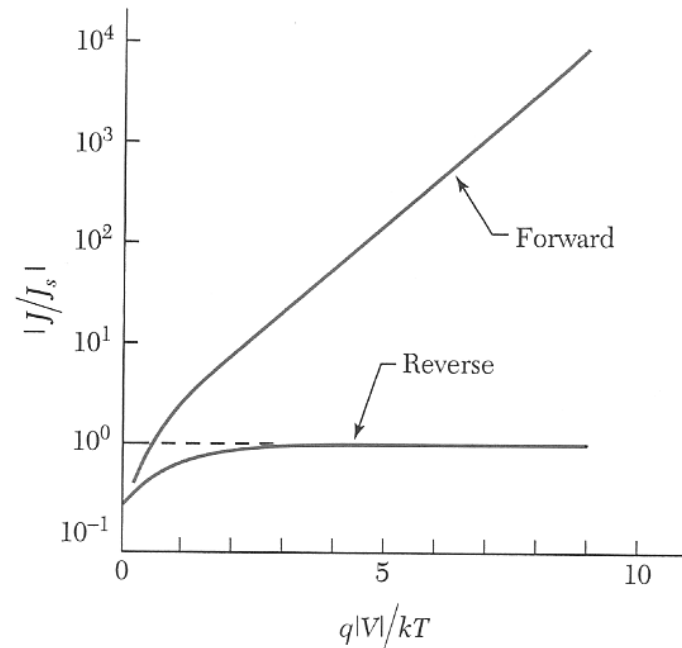
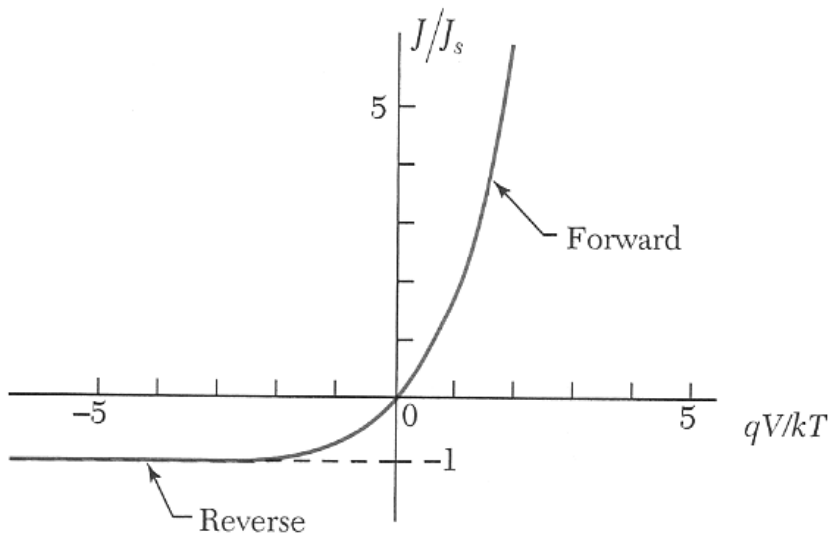
$$J_{diff,p} = \left(p_{n0} \exp\left(\frac{e(V)}{k_B T}\right) - p_{n0} \right) \frac{eD_p}{d_n}$$

$$J_{diff,p} = \frac{p_{n0} eD_p}{d_n} \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right)$$

Short diode current

$$I = eA \left(\frac{p_{n0} D_p}{d_n} + \frac{n_{p0} D_n}{d_p} \right) \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right) = I_s \left(\exp\left(\frac{eV}{k_B T}\right) - 1 \right)$$

Area

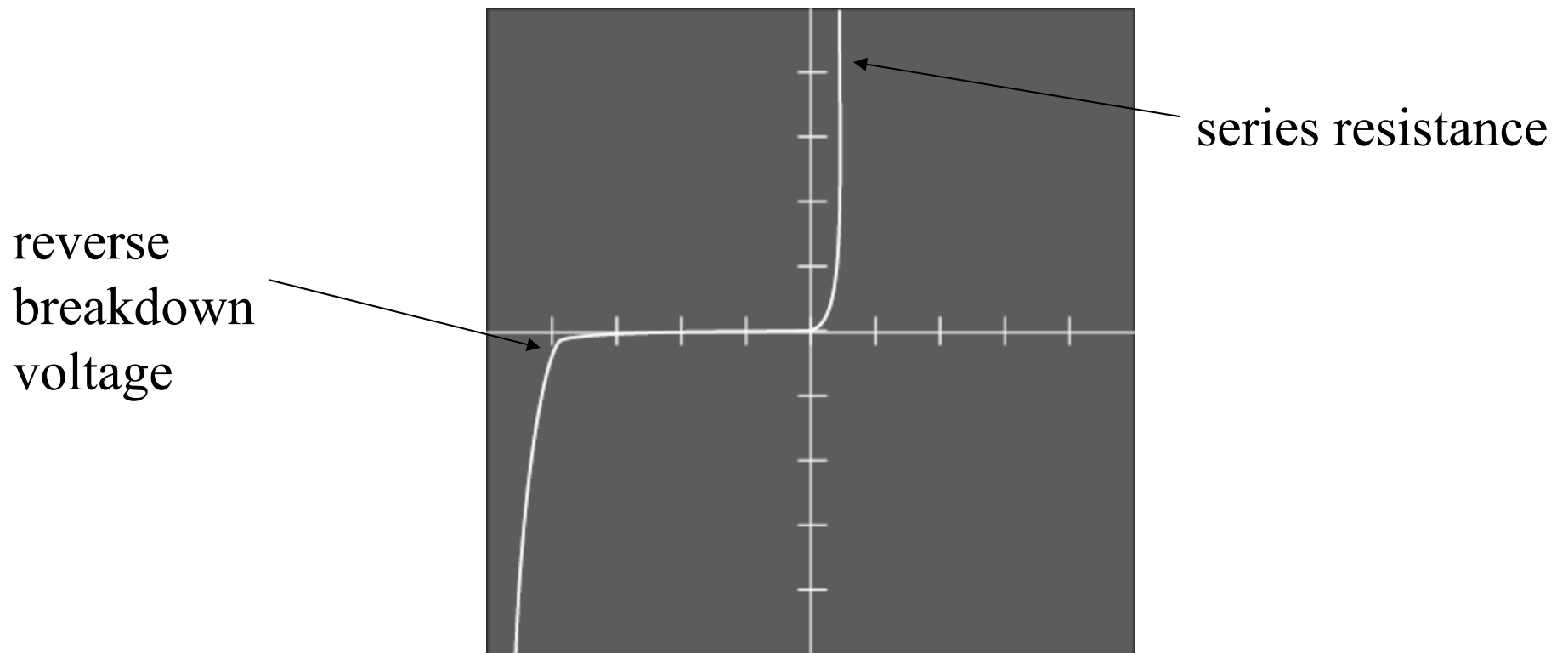


Real diodes

$$I = I_s \left(\exp\left(\frac{eV}{nk_B T}\right) - 1 \right)$$

n = nonideality factor

$n = 1$ for an ideal diode



Real diodes

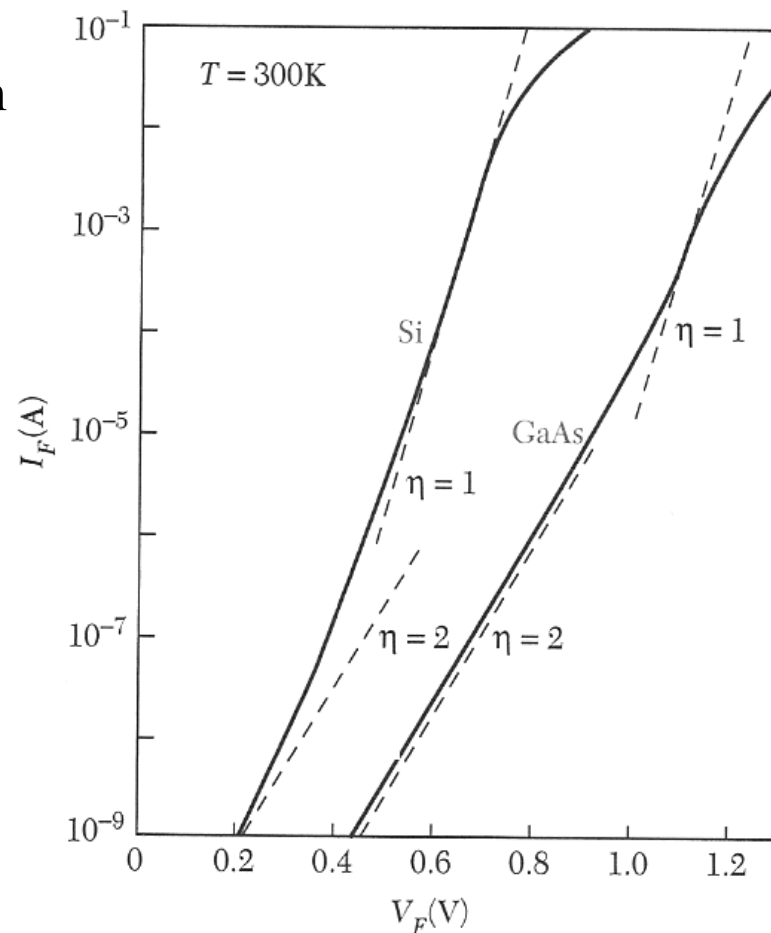
There is constant generation/recombination of electron hole pairs.

In forward bias there is an extra current from recombination.

In reverse bias there is an extra current from generation.

Low bias: recombination dominates, $n = 2$

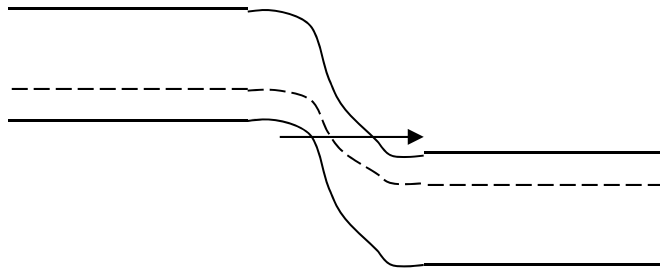
$$I = I_s \left(\exp \left(\frac{eV}{nk_B T} \right) - 1 \right)$$



Very high bias: series resistance

High bias: ideal behavior, $n = 1$

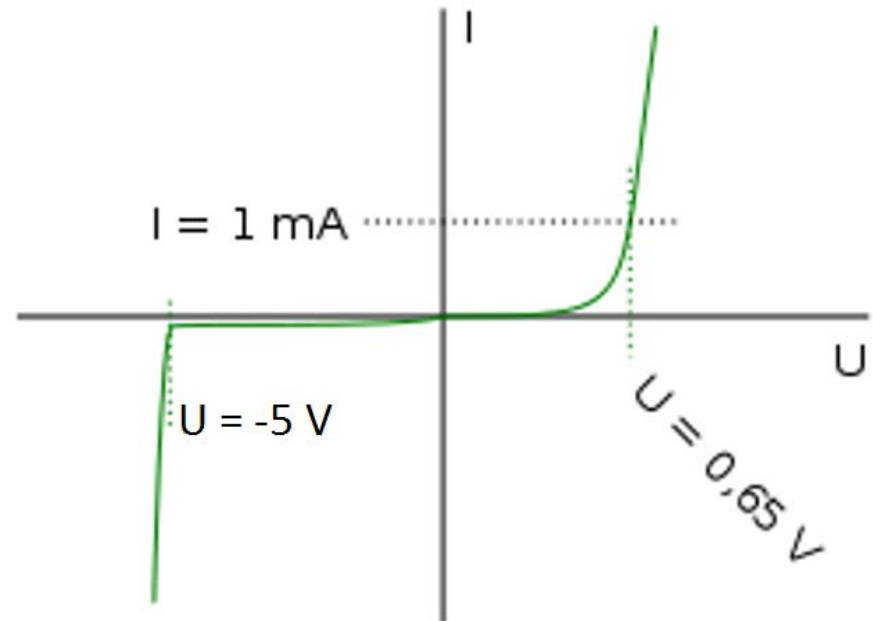
Zener tunneling



Electrons tunnel from valence band to conduction band

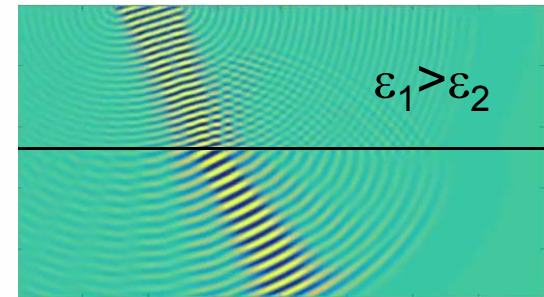
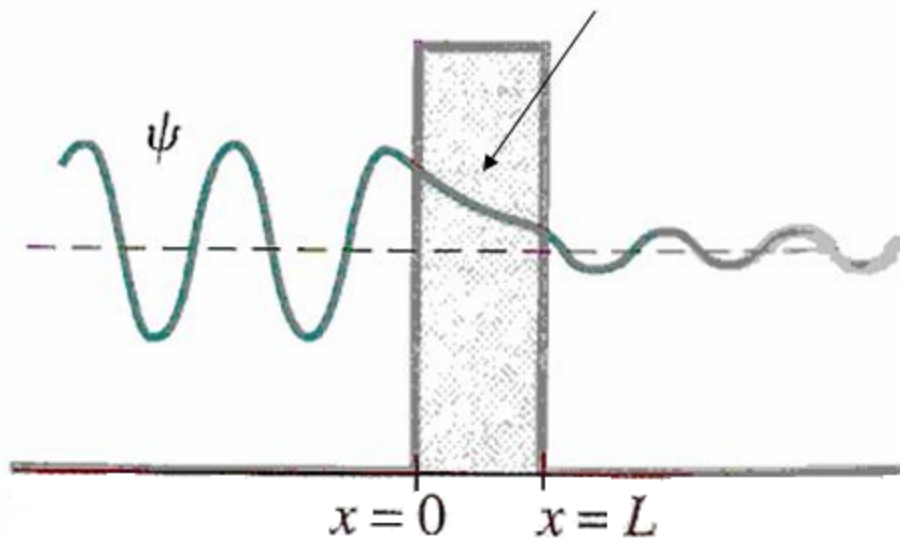
Occurs at high doping

$$|V_{\text{zener}}| < 5.6 \text{ V}$$



Tunneling

wave decays exponentially in the classically forbidden region



Tunneling is a wave phenomena. Tunneling and total internal reflection are used in a beam splitter.

Zener tunneling

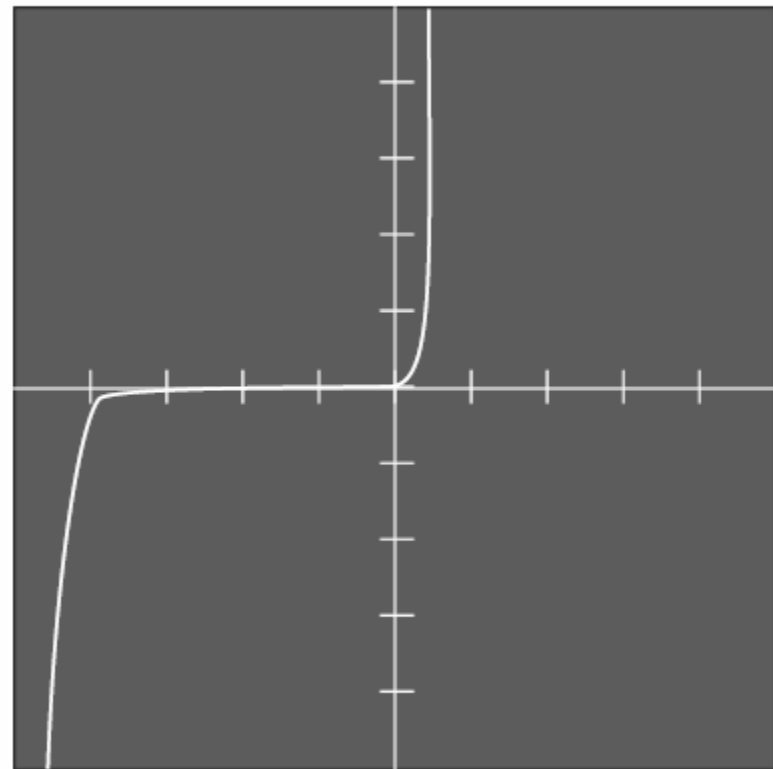
Breakdown voltage is typically much lower than the breakdown voltage of an avalanche diode and can be tuned by adjusting the width of the depletion layer.

Used to provide a reference voltage.

Avalanche breakdown

Impact ionization
causes an avalanche of
current

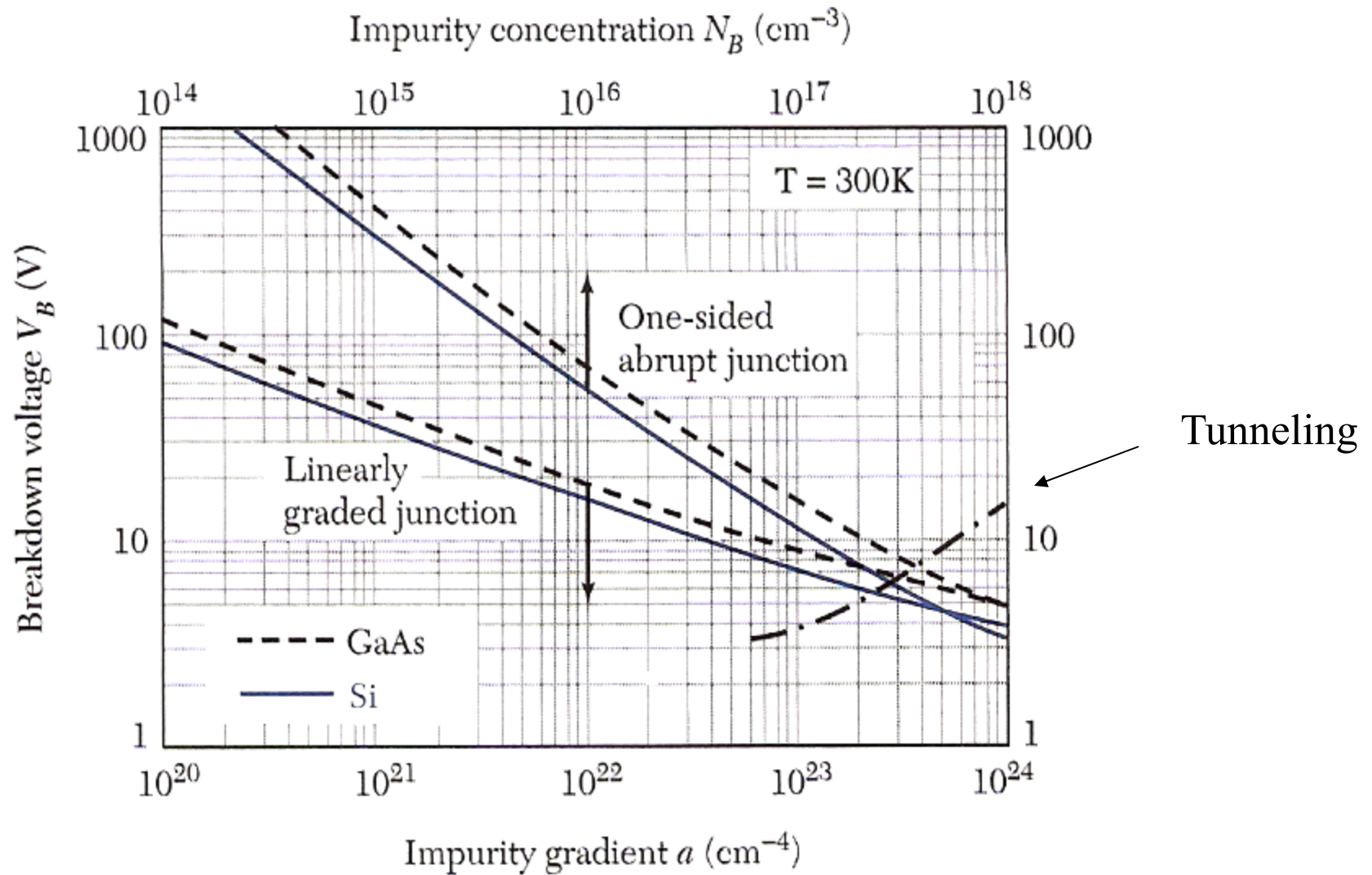
Occurs at low doping



Vertical: 5 mA/div

Horizontal: 5 V/div

Avalanche breakdown



metal - semiconductor contacts

Photoelectric effect
 Workfunction
 Electron affinity
 Interface states
 Schottky barriers
 Schottky diodes
 Ohmic contacts
 Thermionic emission
 Tunnel contacts

